

MICROGAN ECR ION SOURCE IN A VAN DE GRAAFF ACCELERATOR TERMINAL

ABSTRACT

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The Van de Graaff accelerator at IRMM works since many years providing proton, deuteron and helium beams for nuclear data measurements. The original ion source was of RF type with quartz bottle. This kind of source, as well known, needs regular maintenance for which the accelerator tank must be completely opened. The heavy usage at high currents of the IRMM accelerator necessitated an opening about once every month. Recently, the full permanent magnet Microgan ECR ion source from PANTECHNIK was installed into a new terminal platform together with a solid state amplifier of 50W, a dedicated dosing system for 4 gases (with respective gas bottles H2, D2, He and Ar), and a set of dedicated power supplies and electronic devices for the remote tuning of the source. The new system shows a very stable behaviour of the produced beam allowing running the Van de Graff without maintenance for several . months

7 MeV VDG Column filled with up to 15 bars of Nitrogen

with the ECR ion source



MICROGAN ECR ION SOURCE





Usual garanteed intensities (in µAe)							VDG Requirements
lons/Q	1+	2+	3+	4+	5+	8+	1+
Н	7000						60
D							60
He	5000						60
0	4000	400	170				
Р	2000	1200	700	200	20		
Ar	2000	1290	600	220		20	

VAN DE GRAAFF PLATFORM AND CONSTRAINS

Working at High Pressure

- Proof for all parts of the reliability
- Special design (gas dosing valve)
- Dedicated hyperbaric test bench



- Mechanical constrain:
- Small space = need to minimize
- equipments - The machine opening is difficult and time costly =
- * gas system with 4 different kind * full remote control

Electrical constrain:

- About 100 W of AC 400Hz power available at the top of the platform = minimize the total consumption of the equipments
- High Voltage (7MeV) constrain: - Protection against HV sparks for all electronics

10 GHz ECR ION Source using a full permanent magnet field structure

- Components placed in dedicated shielding box
- feed-through and CEM protection placed on each cable (power and signals)



Total charges from the belt of the VdG (max; 200µA):

- Reduce the total ion beam produced
- by reducing the RF power (max. 50 W)
- by reducing the plasma lens aperture (phi 3 mm)

Some specific RF solutions:

- The RF amplifier is a 50W solid state type for 10GHz and is qualified for High Pressure working

- A dedicated Wave Guide (WR90) to coaxial (SMA or N type) feed-through has been developed. The outer is working at 15 bars while the inner side is under vacuum with a rate leak better than 1.10⁻⁹ mbar.l.s⁻¹.



ECRIS 2010

International Workshop on ECR Ion Sources

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